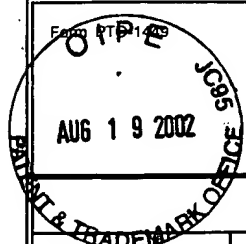


Part of #11

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<b>LIST OF ART CITED BY APPLICANT</b> (Use several sheets if necessary)						APPLICANT Kie Y. Ahn et al.	
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U.S. PATENT DOCUMENTS							
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	AM						
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<i>EK</i>	AR		H.F. Luan et al., "High Quality Ta <sub>2</sub> O <sub>5</sub> Gate Dielectrics with T <sub>ox</sub> < 10Å" International Electron Devices Meeting, pgs. 141-144, 1999. The year of publication is sufficiently early such that the month is not in issue.				
<i>EK</i>	AS		O. Zywitzki et al., "Effect of Plasma Activation on the Phase Transformations of Aluminum Oxide" Surface and Coatings Technology, Vol 76/77, Iss 1/3, pgs. 754-762, 1995. The year of publication is sufficiently early such that the month is not in issue.				
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EXAMINER			DATE CONSIDERED				
<i>Erik Kuehn</i>			<i>10/5/02</i>				
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